

LIST OF PRIOR ART CITED BY APPLICANT
(Filed on January 7, 2004)Docket No. **GK-ZEI-3262 / 500343.20282**Applicant(s): **Thomas ENGEL, Wolfgang HARNISCH, Peter HOFFROGGE and Axel ZIBOLD**

Application No. (Int'l Appln No. PCT/EP03/07401 09JUL03) Group:

Filed: Examiner:
/Sunray R. Chang/ (09/09/2008)**U.S. PATENT DOCUMENTS**

Exam. Init		Document Number	Date	Name	Class	Sub-Class	Filing Date Appropriate
	AA	4,698,236	10/06/1987	Kellogg, et al.			
	AB	5,055,696	10/08/1991	Haraichi, et al.			
	AC	5,148,024	09/15/1992	Watanabe			
	AD	5,808,312	09/15/1998	Fukuda			
	AE	6,016,357	01/18/2000	Neary, et al.			
	AF	6,322,935	11/27/2001	Smith			
	AG	6,353,219	03/05/2002	Kley			
	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	CLASS	Sub-Class	Translation YES	NO
	AL	0 165 685	12/27/1985	European				
	AM	0 298 495	01/11/1989	European				
	AN	0 334 680	09/27/1989	European				
	AO	1 130 465	09/05/2001	European				
	AP	100 30 143	05/31/2001	Germany			Abstract only	
	AQ							
	AR							
	AS							
	AT							

OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	AX	Patent Abstracts of Japan, Publication No. 62-084518, published 18APR87 Hitachi Ltd.
	AY	XP009020507, Use of Nanomachining for Subtractive Repair of EUV and Other Challenging Mask Defects, David Brinkley, et al. Pages 900-911
	AZ	

Examiner: /Sunray R. Chang/ (09/09/2008)

Date:

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /S.C./